

PLASMA EMISSION SYSTEMS FOR ELECTRON- AND ION-BEAM TECHNOLOGIES

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ABSTRACT

Designs and basic characteristics of plasma sources of charged particles allowing one to realize a wide spectrum of electron- and ion-beam technologies are presented. Some applications of the developed structures of charged particles sources are considered. Sketches of promising designs of gas-discharge structures capable of forming combined electron and ion beams are proposed.

KEY WORDS: plasma electron source, low-energy beams, combined ion and electron beams, electron-beams technologies

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